

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:)	
)	Examiner:
Yuichiro Shindo et al.)	
)	Group Art Unit:
Application No.:)	
)	
Corresponding International Filing No.:)	
PCT/JP2005/001488)	
)	
Filed: Herewith)	
)	
For: HIGH-PURITY Ru POWDER,)	
SPUTTERING TARGET)	
OBTAINED BY SINTERING THE)	
SAME, THIN FILM OBTAINED)	
BY SPUTTERING THE TARGET)	
AND PROCESS FOR)	
PRODUCING THE HIGH-PURITY)	
Ru POWDER)	

Mail Stop PCT
 Commissioner for Patents
 P.O. Box 1450
 Alexandria, VA 22313-1450

SECOND PRELIMINARY AMENDMENT

Sir:

Please amend the above-identified patent application as follows.

Amendments to the Specification begin on page two of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page three of this paper.

Remarks begin on page seven of this paper.